



# **FLX 2320-S**

Toho FLX-2320-S Thin Film Stress Measurement Systems offer industry standard capabilities for mass production and research facilities that demand accurate stress measurements on various films and substrates up to 200mm in diameter. Incorporating KLA-Tencor's patented "Dual Wavelength" technology, Toho FLX Series tools determine and analyze surface stress caused by deposited thin films. The Toho FLX systems offer outstanding value in a variety of comprehensive Stress Measurement Solutions that utilize advanced measurement principles.



## **Standard Features**

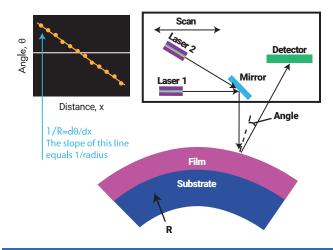
### **Comprehensive Data Analysis**

Intuitive Windows 10 based analysis software displays any combination of stress, time, surface deflection, or reflected light intensity measurements.

- Calculation of biaxial modulus of elasticity, linear expansion coefficient, stress uniformity, and file subtraction
- Trend plotting for Statistical Process Control (SPC)
- · Calculation of water diffusion coefficient in dielectric films
- Automatic recalculation of stress when film or substrate thickness is corrected
- · 2-D and 3-D views of wafer topography
- · Plotting of the measured stress-temperature curve

### **Advanced Laser Technology**

The FLX series feature KLA-Tencor's patented dual wavelength technology, which enables the system to select the wavelength most suitable for challenging films such as silicon nitride. In addition only one moving element in the optical component ensures low vibration and high accuracy.



FLX stress measurement systems use the laser lever technique to measure changes in pre and post deposition surface radii and then correlates these measurements into a stress value.

# **Applications**

In general, stress is induced when materials of dissimilar coefficients of thermal expansion are bonded together. Films may behave similarly at high temperatures but as films are cooled, materials may contract/expand differently, thus causing stress in the film. With a stressed film, defects such as dislocations, voids, and cracking may occur. The FLX stress measurement system helps troubleshoot applications listed below:

- Aluminum stress-inducedvoid
- Passivationcracking (nitride oxide)
- Stress-induced dislocations in Si
- Tungsten Silicide cracking
- Stress increase in oxides during temperature cycling
- Matchingmetallization expansion on GaAs
- Si cracking due to high film stress

#### **Toho Technology Inc.**

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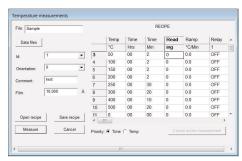
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# THERMAL STRESS Measurement

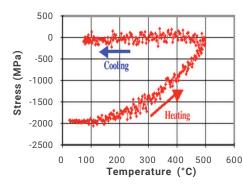
## FLX 2320-S

Temperature measurements are essential for characterizing material properties such as stress relaxation, moisture evolution, and phase changes. Specifically designed for thermal stress applications, the 2320-S is ideal for stress temperature correlations.

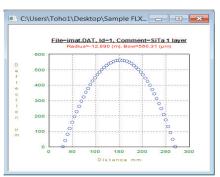
Capable of In-situ stress measurements from Room Temperature to -65°C and from Room Temperture to 500°C with heating rates up to 30°C per minute. The cooling unit which uses LN2 to -65°C is optional.



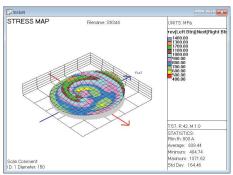
Fully Programmable Temperature Steps







Deflection over Distance Graph



3-D Stress Map

# **Specifications**

#### **Performance**

Scan Range Programmable up to 200mm

Measurement Range 1 to 4,000MPa<sup>1</sup>

Repeatability 1.3MPa<sup>2</sup>

Accuracy Less than 2.5% or 1 MPa (whichever is larger)

Minimim Radius 2.0m Maximum Radius 33km

Wafer Sizes (mm) 25, 50, 75, 100, 150, 200mm

Minimum Scan Step 0.02mm

Compliance Class IIIa 670nm and Class IIIb 780nm 4mW

lasers compliant with 21 CFR, Chapter 1

Subchapter J

#### Notes:

<sup>1</sup> 725µm wafer thickness for 10,000Å thin film

 $^{2}$  (1s): 1 x  $10^{7}$  dyne/cm $^{2}$ 

U.S. Patent No.'s 5134303 and 5248889

# **Options**

- · 3D AnalysisSoftware
- Calibration Mirror Standards
- · Calibration Wafer Standards
- · SubAmbient (-65°C) capability
- SubstrateAdaptor Rings
- Gas Panel with all flow meters and pressure gauges
- Offline Software

## **Computer Specifications**

Win 10 OS, Intel Core i7, 2.9 GHz, 8GB RAM, 1 TB HD, USB ports, DVD-RW Optical Drive, 17" TFT Color Monitor

Specifications subject to change.

